

Patent Application  
10/010,162

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Amendment after Final Rejection  
Expedited Handling Requested - GAU 2812.

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Fwu-Iuan Hshieh et al.  
Serial No.: 10/010,162  
Filed: November 20, 2001  
Title: Method Of Forming Narrow Trenches In Semiconductor Substrates  
Art Unit: 2812  
Examiner: Angel Roman  
Docket No.: GS 149

Via Facsimile 703-872-9319

Commissioner for Patents  
PO Box 1450  
Alexandria, VA 22313-1450

**AMENDMENT AFTER FINAL REJECTION**

Sir:

In response to the Office Action dated December 29, 2003, the time for response ending on Monday, March 1, 2004 (February 29, 2004 being a Sunday), kindly amend the above-identified application as follows. In addition, any deficiencies may be charged to deposit account No. 50-1047.